

GROUP 1752  
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re application of

Kenichiro SATO, et al.

Appln. No.: 09/541,597

Group Art Unit: 1752

Confirmation No.: 4840

Examiner: Rosemary E. ASHTON

Filed: April 03, 2000

For: POSITIVE PHOTORESIST COMPOSITION FOR FAR ULTRAVIOLET  
EXPOSURE

PRELIMINARY AMENDMENT

ATTN: BOX CPA

Commissioner for Patents

Washington, D.C. 20231

Sir:

In response to the Final Office Action dated July 23, 2001, filed concurrently herewith is a request for a Continued Prosecution Application. A Petition for a three month extension of time is also being concurrently filed, making a response due on or before May 21, 2002. (A Notice of Appeal having been filed December 21, 2001). Please amend the above-identified application as follows:

IN THE CLAIMS:

Please enter the following amended claim 9:

9 (twice amended). A positive photoresist composition for far ultraviolet exposure, comprising:

(A) a compound capable of generating an acid by the irradiation of an



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